

**AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

**LISTING OF CLAIMS:**

1. (currently amended): A device for wavefront measurement of an optical imaging system by means of a phase-shifting interferometry technique, the device comprising:  
a mask structure which is arranged on an object side, and  
a grating structure which is arranged on an image side,

~~wherein the mask structure has a different dimensionality than the grating structure, and~~  
wherein the mask structure which is arranged on the object side comprises one or more ~~one-dimensional~~ mask structure patterns with a periodicity in exactly one direction, and the grating structure to be arranged on the image side comprises one or more ~~two-dimensional~~ grating structure patterns with a periodicity in exactly two non-parallel directions, or  
wherein the mask structure comprises one or more ~~two-dimensional~~ mask structure patterns with a periodicity in exactly two non-parallel directions, and the grating structure comprises one or more ~~one-dimensional~~ grating structure patterns with a periodicity in exactly one direction.

2. (previously presented): A method for wavefront measurement of an optical imaging system by means of a phase-shifting interferometry technique, the method comprising:  
at least one of:

moving a phase-shifting structure and a detector element laterally relative to the optical imaging system to be measured, and

moving an object-side mask structure laterally relative to the detector element, wherein a pupil image offset occurring owing to the relative lateral movement is taken into account by back calculating interferograms, wherein the interferograms are respectively recorded by the detector element, using a phase-shifting characteristic associated with the lateral movement, or

wherein the pupil image offset is taken into account by a computational correction of wavefront derivatives, obtained from the recorded interferograms, in the direction of lateral movement.

3. (previously presented): The method according to Claim 2, wherein the computational correction of wavefront derivatives in the direction of lateral movement is performed using the relationship:

$$I^{(2)}(n) = \cos(S_x^{(1)} - \frac{\partial S_x^{(1)}}{\partial x} \frac{\Delta x(n-1)}{N} + \frac{2\pi(n-1)}{N}) \quad ,$$

which specifies the intensity values  $I^{(2)}$  of individual detector element pixels as a function of the  $n$ th lateral phase shift with  $S_x^{(1)}$  as errored wavefront derivative in the phase-shifting direction, from which an error-corrected wavefront derivative ( $S_x^{(2)}$ ) is then calculated, wherein  $N$  denotes a total number of phase steps.

4. (original): The method according to Claim 2, carried out with aid of a device according to Claim 1.

5. (original): The method according to Claim 3, carried out with aid of a device according to Claim 1.

6. (previously presented): A device for wavefront measurement of an optical imaging system by means of a phase-shifting interferometry technique, the device comprising:

a mask structure which is arranged on an object side, and

a grating structure which is arranged on an image side,

wherein the mask structure which is arranged on the object side consists essentially of one or more one-dimensional mask structure patterns with a periodicity in exactly one direction, and the grating structure to be arranged on the image side consists essentially of one or more two-dimensional grating structure patterns with a periodicity in exactly two non-parallel directions, or

wherein the mask structure consists essentially of one or more two-dimensional mask structure patterns with a periodicity in exactly two non-parallel directions, and the grating structure consists essentially of one or more one-dimensional grating structure patterns with a periodicity in exactly one direction.